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(71) Applicant (for all designated States except US): PCBU SERVICES, INC. [US/US]; 300 Delaware Avenue, Suite 1269, Wilmington, DE 19801 (US).

(72) Inventors; and

(75) Inventors/Applicants (for US only): BOGGS, Janet [US/US]; 6925 N. 900 East, Brownsburg, IN 46112 (US). BRANDSTADTER, Stephan, M. [US/US]; 3946 N. Washington Boulevard, Indianapolis, IN 47906 (US). CHIEN, John [US/US]; 3318 Humbolt Street, West Lafayette, IN 47906 (US). SHARMA, Vimal [IN/US];

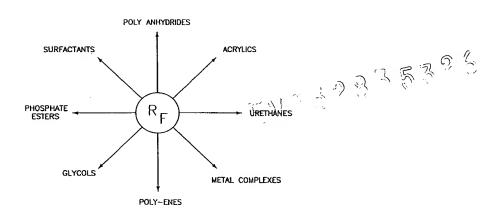
2101 Cumberland Avenue, #5104, West Lafayette, IN 47906 (US). EDWARDS, E., Bradley [US/US]; 3704 Woodcliff Drive, Lafayette, IN 47906 (US). HEDRICK, Victoria, E. [US/US]; 9262 South 300 East, Brookston, IN 47923 (US). JACKSON, Andrew [US/US]; 3346 Whirl Away Court, West Lafayette, IN 47906 (US). LEMAN, Gregory [US/US]; 3319 Crawford Street, West Lafayette, IN 47906 (US). AMEDURI, Bruno [FR/FR]; 26, Rue Louis Roumieux, F-34090 Montpellier (FR). KOSTOV, George, K. [BG/FR]; App. 103, Res Le Mas Vaneau, 189, Rue Edmond Lautard, F-34080 Montpellier (FR).

(74) Agents: HYTA, Robert, C. et al.; Wells St. John P.S., 601 West First Avenue, Suite 1300, Spokane, WA 99201-3828 (US).

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(54) Title: PRODUCTION PROCESSES AND SYSTEMS, COMPOSITIONS, SURFACTANTS, MONOMER UNITS, METAL COMPLEXES, PHOSPHATE ESTERS, GLYCOLS, AQUEOUS FILM FORMING FOAMS, AND FOAM STABILIZERS



(57) Abstract: Production processes and systems are provided that include reacting halogenated compounds, dehalogenating compounds, reacting alcohols, reacting olefins and a saturated compounds, reacting reactants having at least two -CF<sub>3</sub> groups with reactants having cyclic groups. R<sub>F</sub>-compositions such as R<sub>F</sub>-intermediates, R<sub>F</sub>-surfactants, R<sub>F</sub>monomers, R<sub>F</sub>-monomer units, R<sub>F</sub>-metal complexes, R<sub>F</sub>-phosphate esters, R<sub>F</sub>-glycols, R<sub>F</sub>urethanes, and/or R<sub>F</sub>-foam stabilizers. The R<sub>F</sub> portion can include at least two -CF<sub>3</sub> groups, at least three -CF<sub>3</sub> groups, and/or at least two -CF<sub>3</sub> groups and at least two -CH<sub>2</sub>- groups. Detergents, emulsifiers, paints, adhesives, inks, wetting agents, foamers, and defoamers including the R<sub>F</sub>-surfactant composition are provided. Acrylics, resins, and polymers are provided that include a R<sub>F</sub>-monomer unit. Compositions are provided that include a substrate having a R<sub>F</sub>-composition thereover. Aqueous Film Forming Foam ("AFFF") formulations are provided that can include R<sub>F</sub>surfactants and/or R<sub>F</sub>-foam stabilizers are provided.



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